



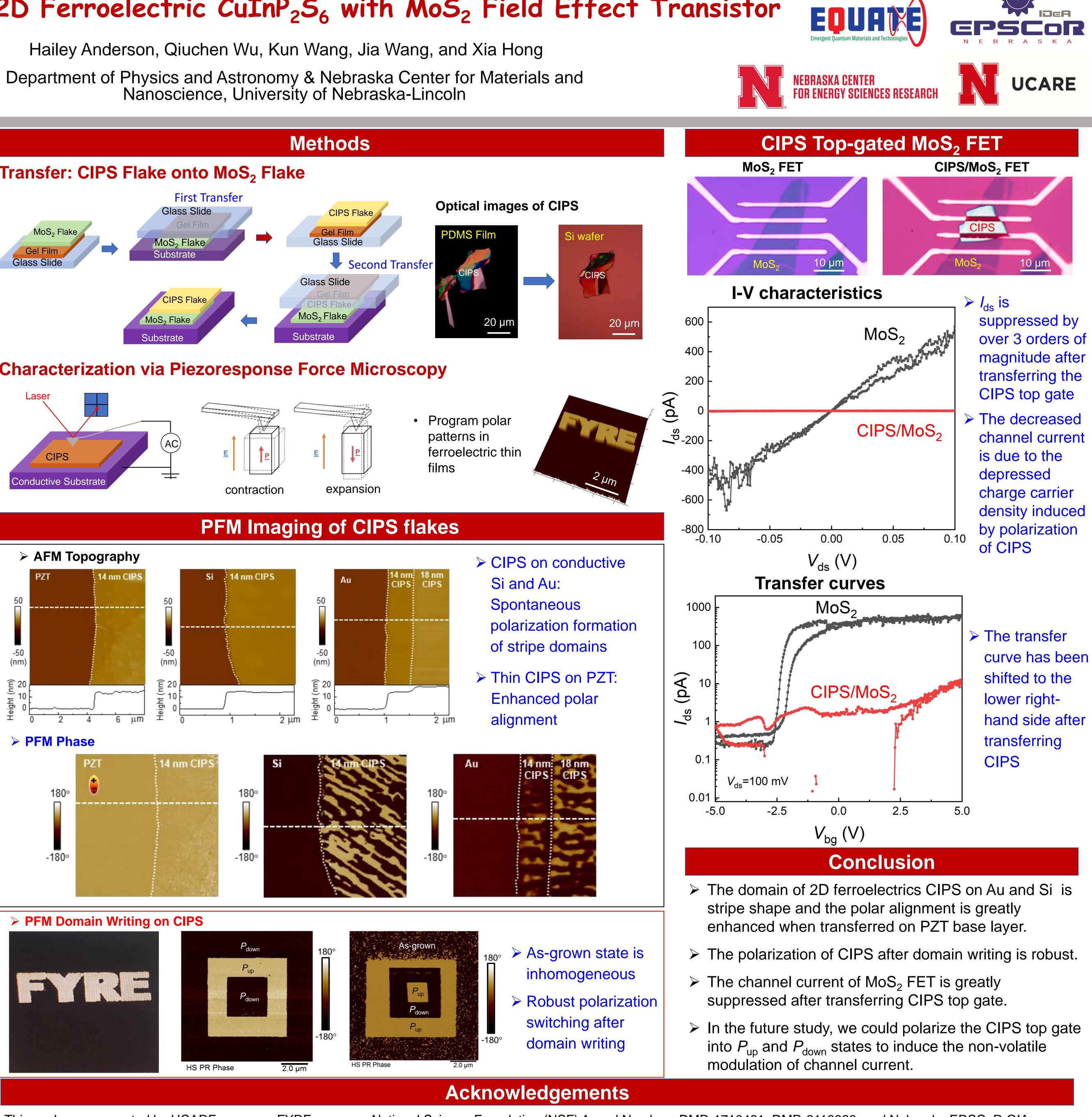
Integrating 2D Ferroelectric $CuInP_2S_6$ with MoS_2 Field Effect Transistor

Abstract

This study examined the gating effect of two dimensional (2D) van der Waals (vdW) ferroelectrics CuInP₂S₆ (CIPS) in modulation of channel current of 2D semiconductor MoS₂ field effect transistor (FET). Recently, ferroelectricity has been discovered in 2D vdW materials, such as SnTe, In₂Se₃, and CIPS. These materials can potentially preserve ferroelectricity in the monoatomic layer limit, making them promising for developing ferroelectric-based 2D nanoelectronics.

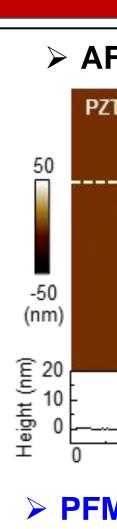
In this study, we explored the gating effect on 2D MoS₂ FET top gated by 2D vdW ferroelectrics CIPS. The polarizations of CIPS on different base layers are robust after domain writing using conductive atomic force microscopy (AFM). The channel conductance has been sufficiently suppressed after transferring the CIPS top gate on MoS₂, which is due to the charge carrier depletion induced by the polarization of as-grown CIPS. In the future study, we could use piezoresponse force microscopy (PFM) to switch the polarization of the CIPS top gate into the P_{up} and P_{down} states, which might induce non-volatile modulation of channel current and achieve the different current on/off ratios. Our research can provide important material parameters for designing CIPSbased nanoelectronic devices, paving the path for their implementation in programmable, flexible nonvolatile memory, neuromorphic computing, and optoelectronic applications.

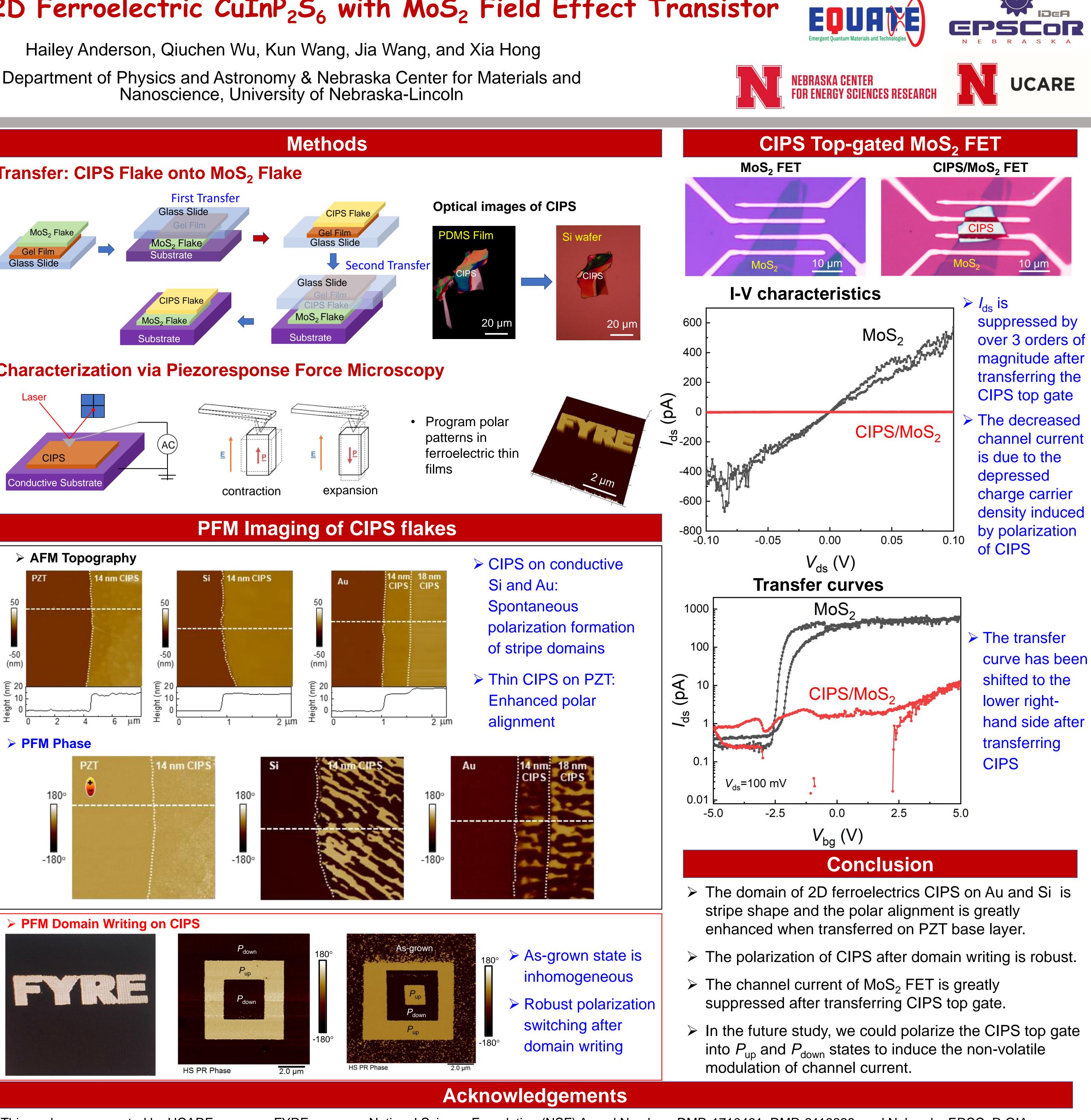
Introduction

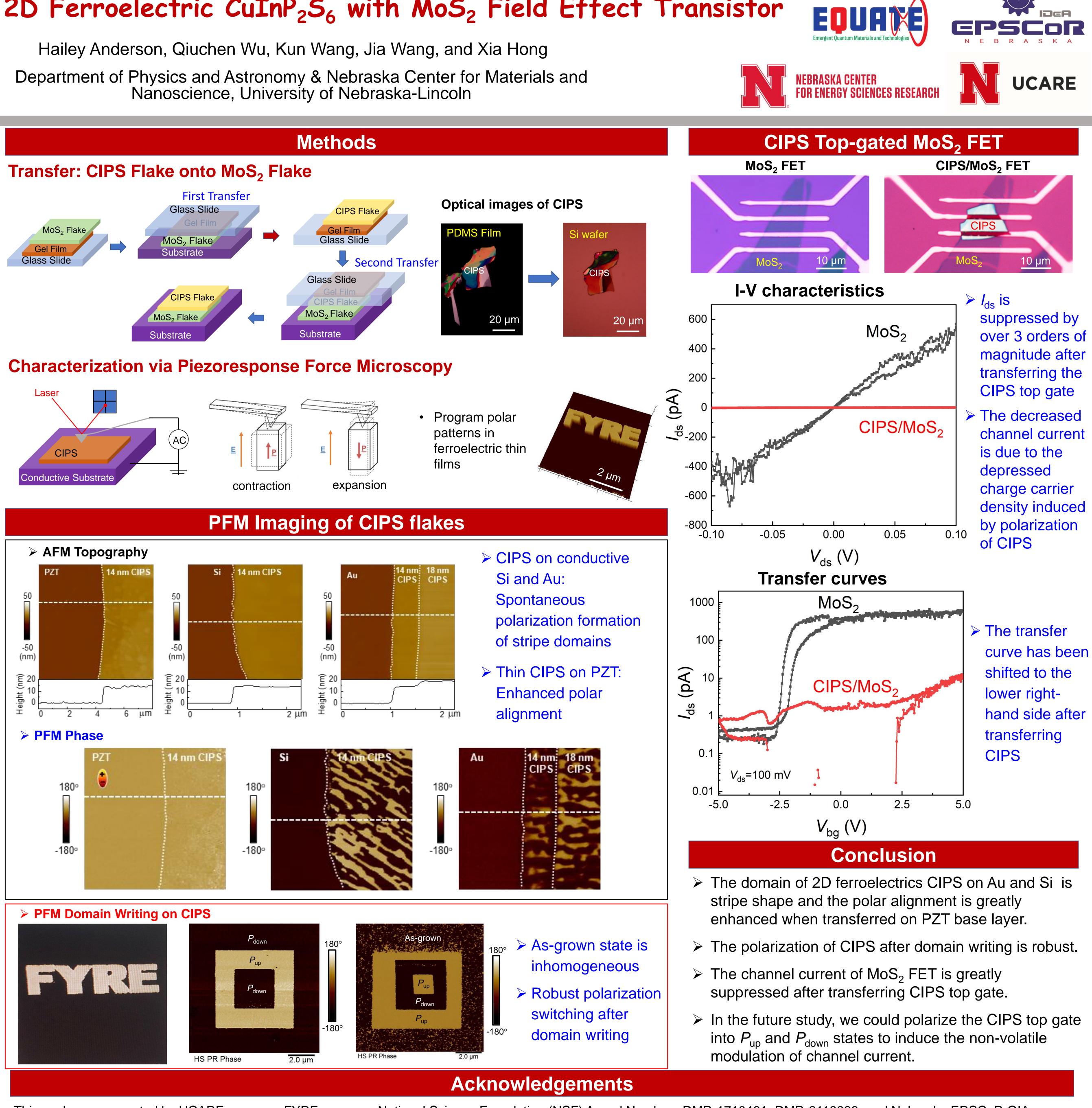


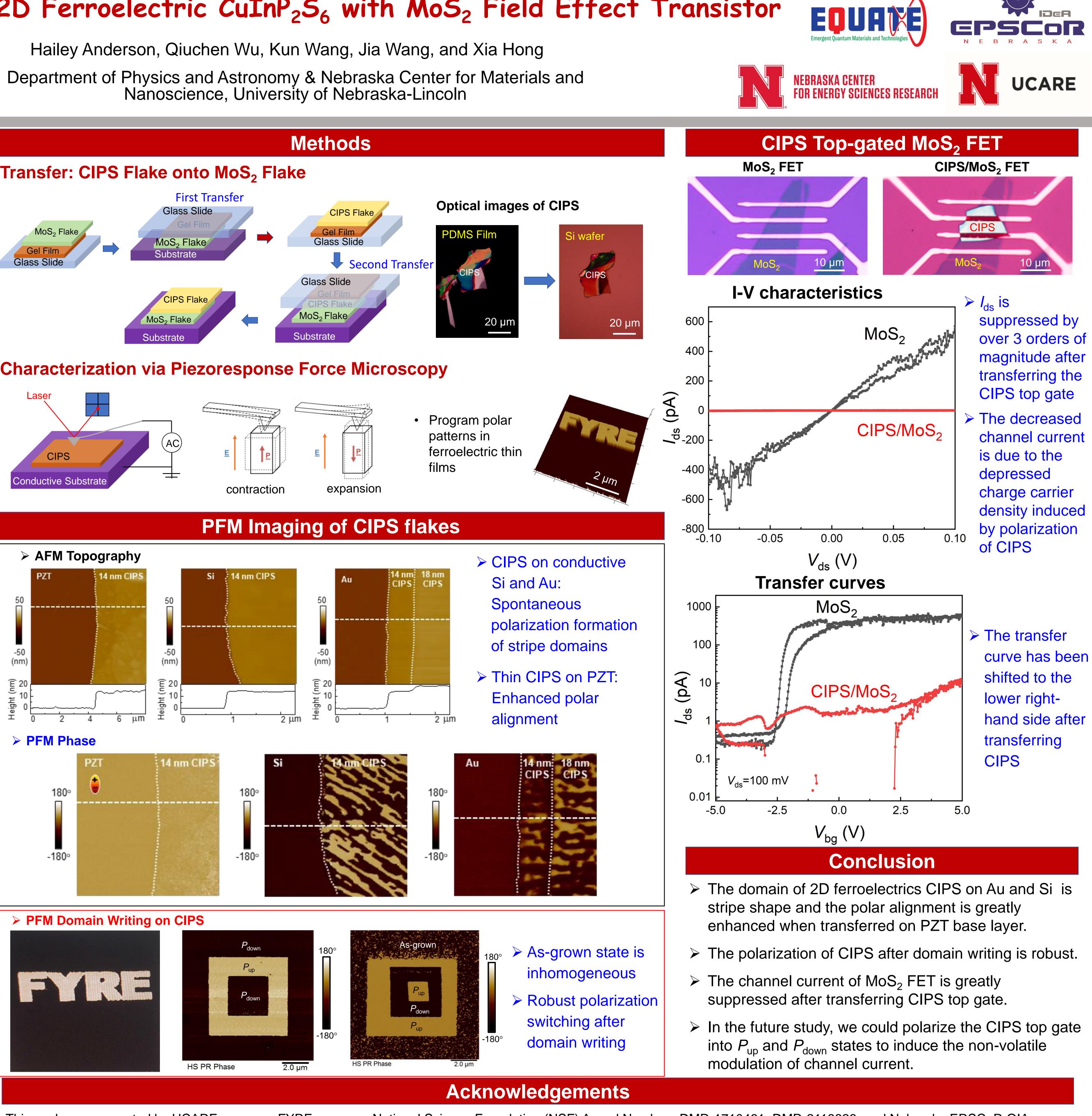








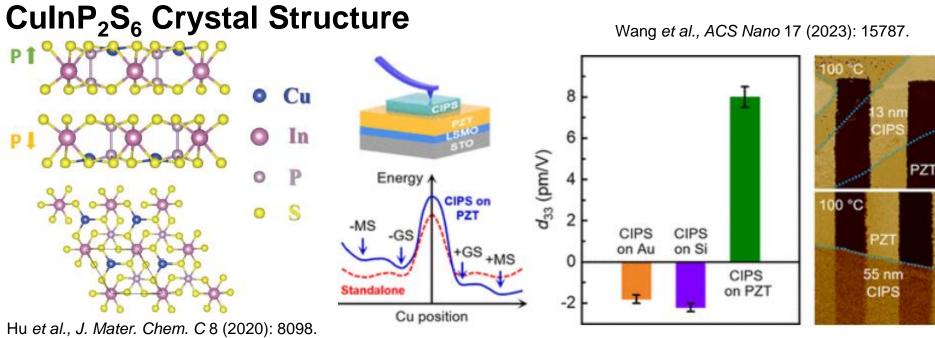




∽DW • Ferroelectric shows the piezoelectric response under external

electric fields • Non-volatile polarization and switchable hysteresis

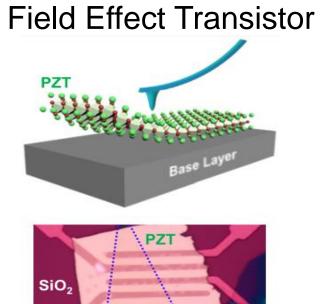
2D van der Waals (vdW) Ferroelectrics



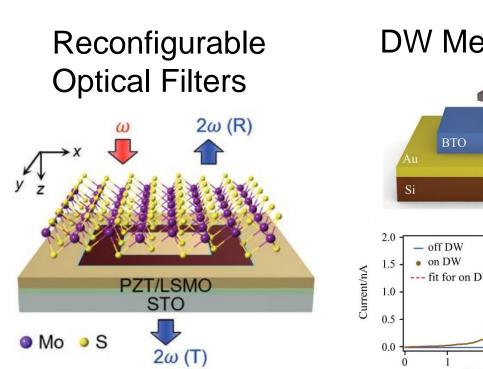
• 2D vdW ferroelectrics can preserve ferroelectricity in the atomic layer limit, which is compromised for conventional ferroelectrics

Application

Ferroelectrics



Wu et al., ACS Nanosci. Au 3 (2023): 482



Li et al., Adv. Mater. 35 (2023): 2208825

DW Memories -- fit for on DW 1 2 3 4 Voltage/V 4

Sun et al., Nat Commun 13 (2022): 4332.

2044049, and Nebraska Center for Energy Sciences Research (NCESR).



